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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Leonard Forbes et al.

GETTERING USING VOIDS FORMED BY SURFACE TRANSFORMATION

Docket No.:

1303.108US1

Serial No.: 10/623794

Filed:

July 21, 2003

Due Date: N/A

Examiner:

Unknown

Group Art Unit: 2811

MS Amendment

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

We are transmitting herewith the following attached items (as indicated with an "X"):

X A return postcard.

X A Communication Concerning Related Applications (3 pgs.).

X An Information Disclosure Statement (2 pgs.), Form 1449 (11 pgs.), and copies of 111 cited documents.

If not provided for in a separate paper filed herewith, Please consider this a PETITION FOR EXTENSION OF TIME for sufficient number of months to enter these papers and please charge any additional fees or credit overpayment to Deposit Account No. 19-0743.

SCHWEGMAN, LUNDBERG, WOESSNER & KLUTH, P.A.

Customer Number 21186

Atty: Marvin L. Beekman

Reg. No. 38,377

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Name

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SCHWEGMAN, LUNDBERG, WOESSNER & KLUTH, P.A.

(GENERAL)



S/N 10/623794 PATENT

IN THE REPETED STATES PATENT AND TRADEMARK OFFICE

Applicant:

Leonard Forbes et al.

Examiner: Unknown

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July 21, 2003

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Title:

GETTERING USING VOIDS FORMED BY SURFACE TRANSFORMATION

COMMUNICATION CONCERNING RELATED APPLICATION(S)

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Applicants would like to bring to the Examiner's attention the following related application(s) in the above-identified patent application:

Serial/Patent No. 10/052952	Filing Date January 17, 2002	Attorney Docket 1303.034US1	Title THREE-DIMENSIONAL PHOTONIC CRYSTAL WAVEGUIDE STRUCTURE AND METHOD
10/382246	March 5, 2003	1303.086US1	CELLULAR MATERIALS FORMED USING SURFACE TRANSFORMATION
10/379749	March 5, 2003	1303.089US1	MICRO-MECHANICALLY STRAINED SEMICONDUCTOR FILM
10/425797	April 29, 2003	1303.093US1	LOCALIZED STRAINED SEMICONDUCTOR ON INSULATOR
10/431134	May 7, 2003	1303.094US1	STRAINED Si/SiGe STRUCTURES BY ION IMPLANTATION
10/425484	April 29, 2003	1303.095US1	STRAINED SEMICONDUCTOR BY WAFER BONDING WITH MISORIENTATION
10/443340	May 21, 2003	1303.099US1	ULTRA-THIN SEMICONDUCTORS BONDED ON GLASS SUBSTRATES
10/431137	May 7, 2003	1303.100US1	MICROMECHANICAL STRAINED SEMICONDUCTOR BY WAFER BONDING
10/634174	August 5, 2003	1303.102US1	STRAINED Si/SiGe/SOI ISLANDS AND PROCESSES OF MAKING SAME

COMMUNICATION CONCERNING RELATED APPLICATIONS Serial Number: 10/623794

Filing Date: July 21, 2003
Title: GETTERING USING VOIDS FORMED BY SURFACE TRANSFORMATION

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10/443337	May 21, 2003	1303.103US1	GETTERING OF SILICON ON INSULATOR USING RELAXED SILICON GERMANIUM EPITAXIAL PROXIMITY LAYERS
10/443339	May 21, 2003	1303.104US1	WAFER GETTERING USING RELAXED SILICON GERMANIUM EPITAXIAL PROXIMITY LAYERS
10/623788	July 21, 2003	1303.109US1	STRAINED SEMICONDUCTOR BY FULL WAFER BONDING
09/855532	May 16, 2001		METHOD OF FORMING MIRRORS BY SURFACE TRANSFORMATION OF EMPTY SPACES IN SOLID STATE MATERIALS
09/861770 6582512	May 22, 2001		METHOD OF FORMING THREE- DIMENSIONAL PHOTONIC BAND STRUCTURES IN SOLID MATERIALS
09/734547 6383924	December 13, 2000		METHOD OF FORMING BURIED CONDUCTOR PATTERNS BY SURFACE TRANSFORMATION OF EMPTY SPACES IN SOLID STATE MATERIALS
10/118350	April 9, 2002		METHOD OF FORMING SPATIAL REGIONS OF A SECOND MATERIAL IN A FIRST MATERIAL
10/093332	March 7, 2002		METHOD AND APPARATUS FOR PACKAGING SEMICONDUCTOR DEVICES

COMMUNICATION CONCERNING RELATED APPLICATIONS

Serial Number: 10/623794 Filing Date: July 21, 2003

Title: GETTERING USING VOIDS FORMED BY SURFACE TRANSFORMATION

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Respectfully submitted,

LEONARD FORBES ET AL.

By Applicants' Representatives,

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Date 5-10-04

Reg. No. 38,377

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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Unknown

10/623794

Group Art Unit:

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Title:

GETTERING USING VOIDS FORMED BY SURFACE TRANSFORMATION

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

In compliance with the duty imposed by 37 C.F.R. § 1.56, and in accordance with 37 C.F.R. §§ 1.97 et. seq., the enclosed materials are brought to the attention of the Examiner for consideration in connection with the above-identified patent application. Applicants respectfully request that this Information Disclosure Statement be entered and the documents listed on the attached Form 1449 be considered by the Examiner and made of record. Pursuant to the provisions of MPEP 609, Applicants request that a copy of the 1449 form, initialed as being considered by the Examiner, be returned to the Applicants with the next official communication.

Pursuant to 37 C.F.R. §1.97(b), it is believed that no fee or statement is required with the Information Disclosure Statement. However, if an Office Action on the merits has been mailed, the Commissioner is hereby authorized to charge the required fees to Deposit Account No. 19-0743 in order to have this Information Disclosure Statement considered.

The Examiner is invited to contact the Applicants' Representative at the below-listed telephone number if there are any questions regarding this communication.

The present application is either a U.S. national patent application filed after June 30, 2003 or an international application that entered the national stage under 35 U.S.C. § 371 after June 30, 2003. Thus, Applicant believes that the U.S. Patent & Trademark Office has waived the requirement under 37 C.F.R. 1.98 (a)(2)(i) for submitting a copy of each cited U.S. patent and each U.S. patent application publication. The waiver is provided in a pre-OG notice from the U.S. Patent & Trademark Office entitled "Information Disclosure Statements May Be Filed Without Copies of U.S. Patents and Published Applications in Patent Applications filed after

Serial No :10/623794

Dkt: 1303.108US1

Filing Date: July 21, 2003

Title: GETTERING USING VOIDS FORMED BY SURFACE TRANSFORMATION

June 30, 2003" and dated July 11, 2003. Applicant acknowledges the requirement to submit copies of foreign patent documents and non-patent literature in accordance with 37 C.F.R. 1.98(a)(2).

Respectfully submitted,

LEONARD FORBES ET AL.

By their Representatives,

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Date 5-10-04

Bv

Marvin L. Beekman Reg. No. 38,377

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JAMES E. KAN XUIK

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PTO/SB/08A(10-01)

Approved for use through 10/31/2002. OMB 651-0031

US Patent & Trademark Office: U.S. DEPARTMENT OF COMMERCE

Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number. Substitute for form 1449A/PTO Complete if Known INFORMATION DISCLOSURE 10/623794 **Application Number** EMENT BY APPLICANT July 21, 2003 **Filing Date** (Use as many sheets as necessary) **First Named Inventor** Forbes, Leonard 2811 **Group Art Unit Examiner Name** Unknown

Attorney Docket No: 1303.108US1

Sheet 1 of 11

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Examiner Initial *	USP Document Number	Publication Date	Name of Patentee or Applicant of cited Document	Class	Subclass	Filing Date If Appropriate
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EXAMINER

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(Use as many sheets as necessary)	Filing Date	July 21, 2003
	First Named Inventor	Forbes, Leonard
	Group Art Unit	2811
	Examiner Name	Unknown
Sheet 2 of 11	Attorney Docket No: 1	1303.108US1

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Substitute for form 1449A/PTO Complete if Known INFORMATION DISCLOSURE 10/623794 **Application Number** STATEMENT BY APPLICANT July 21, 2003 **Filing Date** (Use as many sheets as necessary) Forbes, Leonard **First Named Inventor** 2811 **Group Art Unit** Unknown **Examiner Name** Attorney Docket No: 1303.108US1 Sheet 3 of 11

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PTO/SB/08A(10-01)

Approved for use through 10/31/2002, OMB 651-0031

US Patent & Trademark Office: U.S. DEPARTMENT OF COMMERCE

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(Use as many sheets as necessary)	Filing Date	July 21, 2003
	First Named Inventor	Forbes, Leonard
	Group Art Unit	2811
	Examiner Name	Unknown
Sheet 4 of 11	Attorney Docket No: 1	303.108US1

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Substitute for form 1449A/PTO	Complete if Known				
INFORMATION DISCLOSURE STATEMENT BY APPLICANT	Application Number	10/623794			
(Use as many sheets as necessary)	Filing Date	July 21, 2003			
	First Named Inventor	Forbes, Leonard 2811			
	Group Art Unit				
	Examiner Name	Unknown			
Sheet 5 of 11	Attorney Docket No: 1	303.108US1			

	OTHE	R DOCUMENTS NON PATENT LITERATURE DOCUMENTS	
Examiner Initials*	Cite No ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T²
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